

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					CT-M158 US		09/896,249	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicants			
(Use additional sheets if necessary)					Pei, Shiyu, et al.			
					Filing Date		Group	
					June 28, 2001		2879	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
WJN	AA	4,919,157	04/24/90	Mateias	134	2		
	AB	5,559,389	09/24/96	Spindt et al.	313	310		
	AC	5,564,959	10/15/96	Spindt et al.	445	24		
	AD	5,605,484	02/25/97	Bailey et al.	445	59		
	AE	5,635,790	06/03/97	Meyer et al.	313	309		
	AF	5,853,492	12/29/98	Cathey et al.	134	3		
	AG	5,977,706	11/02/99	Cho et al.	313	553		
	AH	6,004,180	12/21/99	Knall et al.	445	59		
	AI	6,113,708	09/05/00	Hopple et al.	134	7		
	AJ	6,139,390	10/31/00	Pothoven et al.	445	41		
KJN	AK	US 6,187,603 B1	02/13/01	Haven et al.	438	20		
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							
	AR							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
	AS							
	AT							
	AU							
	AV							
	AW							
Examiner		Date Considered						
KJN		7/11/03						
*EXAMINER: Initials are considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								

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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)			
14/12	AA	Brodie, et al., "Vacuum Microelectronics," <u>Advances In Electronics And Electron Physics</u> , Vol. 83, 1992, pp. 1 - 106.	
	AB	Chalamala, et al., "Operation of FEAs in Hydrogen and the Development of Thin Film Metal Hydrides for Integration into FEDs", <u>SID 01 Digest</u> , 2001, pp. 89 - 91.	
	AC	Chalamala, et al., "Residual Gas Effects on the Emission Characteristics of Active Mo Field-Emission Cathode Arrays," <u>SID 98 Digest</u> , 1998, pp. 107 - 110.	
	AD	Chalamala, et al., "Surface conditioning of active molybdenum field emission cathode arrays with H <sub>2</sub> and helium," <u>J. Vac. Sci. Technol.</u> , Sept/Oct 1998, pp. 2855 - 2858.	
	AE	Hopple, et al., "FED Life and Reliability," <u>Information Display</u> , April/May 2000, pp. 34 - 37.	
	AF	Jo, et al., "Analysis of field emission characteristics of hydrogen-adsorbed silicon surface," <u>Appl. Phys. Lett.</u> , 15 April 1996, pp. 2234 - 2236.	
	AG	Kim, et al., "High-Resolution 5-8in. Full-Color FEDs with New Aging Technique," <u>Proceedings of SID'98</u> , Int'l. Symp., 17 - 22 May 1998, 4 pgs.	
	AH	Reuss, et al., "New Insights Into the Degradation of Field Emission Displays," <u>SID 01 Digest</u> , 2001, pp. 81 - 83.	
K/12	AI	Schwoebel, et al., "Field-emitter array performance enhancement using hydrogen glow discharges," <u>Appl. Phys. Lett.</u> , July 1993, pp. 33 - 35.	
	AJ		
	AK		
	AL		
	AM		
Examiner		Date Considered	
KENNETH J. RAMSEY PRIMARY EXAMINER		7/11/03	
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